Spatial-Phase Locked E-Beam Lithography
\( \sigma = 1\text{nm} \) Field Stitching Precision

- Vertical Boundary, X-Stitching:
  - \( \sigma = 1.0\text{nm}, \mu = 1.4\text{nm} \)
  - \( \sigma = 1.1\text{nm}, \mu = 2.5\text{nm} \)

- Horizontal Boundary, X-Stitching:
  - \( \sigma = 1.2\text{nm}, \mu = -1.4\text{nm} \)
  - \( \sigma = 1.3\text{nm}, \mu = -1.0\text{nm} \)